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(54) Title: **SILYL ALKYL ESTERS OF ANTHRACENE- AND PHENANTHRENE CARBOXYLIC ACIDS**

(57) Abstract: The invention relates to silyl alkyl esters, in particular of anthracene and phenanthrene carboxylic acids, a process for their preparation, compositions and polysiloxane compositions which contain the silyl alkyl esters and which can be used in particular in the semiconductor industry for the preparation of anti-reflective layers for photolithographic applications.

WO 2004/000853 A1